

IN THE SPECIFICATION

At page 7, please make the following amendments to paragraphs 0020:¹⁹

Figure 3 depicts a layer 310 disposed on underlying layer 205 after a zeolite – sol colloid, such as zeolite – sol colloid 115 as shown in Figure 1, has been deposited on underlying layer 205 through deposition process 305. The zeolite – sol colloid may be deposited on underlying layer 205 in any variety of known methods. For example, the zeolite – sol colloid may be deposited by dip-coating underlying layer 205 in the zeolite – sol colloid. As another example, the zeolite – sol colloid may be deposited by spin-coating the zeolite – sol colloid on underlying layer 205. It is readily apparent that these well-known methods, as well as other well-known methods, of depositing dielectric material may be used to deposit the zeolite – sol colloid on underlying layer 205.

At page 8, please make the following amendments to paragraphs 0024:²³

Furthermore, as shown in Figure 5, approximately any remaining liquid in the wet gel (previously formed from a zeolite – sol colloid) may be extracted to form aerogel – zeolite composite 510 through extraction step 605. By using different extraction conditions (vacuum, temperatures, various extraction rate), the resulting aerogel – zeolite composite 510 is variable to obtain different mechanical properties and k values. The extraction of the remaining liquid may be done by the same methods aforementioned in reference to extraction step 405 shown in Figure 4.

At page 9, please make the following amendments to paragraphs 0026:²⁵

Referring to Figure 7 and Figure 8 further damascene processing may be done on the wet gel – zeolite or aerogel – zeolite composite film. To simply further damascene processing, Figures 7 and